SUBSTITUTE FORM PTO-1449 U.S. DEPARTMENT OF (MODIFIED) PATENT AND TRADEM												ATTY. SSIT-1				SERIAL NO. 10/711,649	
										OSURE LICANT	•	APPLICANT Kawamura et at.					
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MDIT		B.A	4 3 4 1 5 9		2	07/27/1982	Shortes et al.		156	643		08/04/1975					
		B.B	4	3	4	9	4	1	5	09/14/1982	DeFilippi et al.		204	14		08/28/1979	
		B.C	4	3	5	5	9	3	7	10/26/1982	Mack et al.		414	217		12/24/1980	
		B.D	4	3	6	7	1	4	0	01/04/1983	Wilson		210	110		10/30/1980	
	1	B.E	4	4	0	6	5	9	6	09/27/1983	Budde		417	393		07/27/1981	
	1	B.F	4	4	2	2	6	5	1	12/27/1983	Platts		277	206 R		12/27/1978	
	1	B.G	4	4	7	4	1	9	9	10/02/1984	Blaudszun		134	105		11/09/1982	
		в.н.	4	4	7	5	9	9	3	10/09/1984	Blander et al.		204	64		08/15/1983	
		B.1	4	5	2	2	7	8	8	08/11/1985	Sitek et al.		422	78		03/05/1982	
		B.J	4	5	4	9	4	6	7	10/29/1985	Wilden et al.		91	307		08/03/1983	
		B.K	4	5	9	2	3	0	6	06/03/1986	Gallego		118 719			11/30/1984	
FOREIGN PATENTS OR PUBLISHED FOREIGN PATENT APPLICATIONS																	
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	_	B.L														_	
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		в.Р													<u></u>		
B.Q											•						
OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)																	
mi	المار	B.R Z. Guan et al., Fluorocarbon-Based Heterophase Polymeric Materials. I. Block Copolymer Surfactants for Carbon Dioxide Applications, Macromolecules, Vol. 27, pp 5527-5532, 1994.															
		8.8	International Journal of Environmentally Conscious Design & Manufacturing, Vol. 2, No. 1, pp. 83, 1993.														
7	/	в.т	Matson and Smith , Supercritical Fluids, Journal of the American Ceramic Society, Vol. 72, No. 6, pp. 872-874; 198 9														
EXAMINER DATE CONSIDERED 3/3/06																	
EXAMINER: Initial if citation considered, whether or not in conformance. Draw line through citation only if not in conformance and not considered. Include a copy of this form with next communication to Applicant.																	
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- 	MDH SA			8	8	8	0	5	0	03/30/1999	Fitzgerald et al.		417	46		08/25/1998	
10.0		S.B	5	8	9	3	7	5	6	04/13/1999	Berman et al.		438	692		08/26/1997	
		s.c	5	8	9	6	8	7	0	04/27/1999	Huynh et al.		134	1.3		03/11/1997	
		S.D	5	8	9	8	7	2	7	04/27/1999	Fujikawa et al.		373	110		04/28/1997	
		S.E	5	9	0	0	1	0	7	05/04/1999	Murphy et al.		156	359		09/11/1996	
		S.F	5	9	0	0	3	5	4	05/04/1999	Batchelder		430	395		07/03/1997	
		S.G	5	9	0	4	7	3	7	05/18/1999	Preston et al.		8	158		11/26/1997	
		S.H	5	9	0	в	8	6	6	05/25/1999	Webb		427	534		02/10/1997	
		S.I	5	9	0	8	5	1	0	08/01/1999	McCullough et al.		134	2		10/16/1996	
		S.J	5	9	2	8	3	8	9	07/27/1999	Jevtic	29		25.01		10/21/1996	
\	/	S.K	5	9	3	2	1	0	0	08/03/1999	Yager et al.	et al.		634		06/14/1996	
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MD	1+	S.R	Kawakami et al., A Super Low-k(k=1,1) Silica Aerogel Film Using Supercritical Drying Technique, IEEE, pp. 143-145, 2000.														
		S.S	R. F. Reidy, Effects of Supercritical Processing on Ultra Low-k Films, Texas Advanced Technology Program, Texas Instruments and the Texas Academy of Mathematics and Science, 2002														
V	S.T Anthony Muscat, Backend Processing Using Supercritical CO ₂ , University of Arizona 2003																
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